High-speed digital data communication in FALAPHEL project

<u>28 nm</u> vs. 65 nm technologies for high-speed data communication:

- Higher cut-off frequency 🕑
- Lower area 🕑
- Lower power 🕑
- Higher radiation tolerant 🕑
- Greater effects of parasitic elements 😥
- Higher fabrication cost 😔

High-speed architecture:



High Frequency PADs and ESD protections in 28 nm

Motivations:

- PADs and ESD protections are <u>not provided</u> by TSMC
- High-speed signals require low capacitance pads and protections
- ESD protections are moving from 2 kV to 500 V HBM levels

Submitted on 28/10/20



25 Gb/s Ring Resonator Driver in 28 nm

Layout area: 200 x 120 μ m²

Motivations:

- High-speed communication on optical fibers
- Silicon Photonic as promising technology for electro-optical modulation
- 28 nm technology to reduce the gap with the optical speed
- P-type MOSFETs avoided for radiation hardness increment



Submitted on 28/10/20







Characteristic:

- 50 Ω output resistance
- ±500mV output amplitude .
- Passive and active bandwidth enhancement
- Common mode correction

25 GHz LC-tank VCO in 28 nm

Motivations:

- High-speed clock signal for on-chip digital systems (elaboration and transmission)
- Ring oscillators designed in 28 nm showed large PVT variation

Submitted on 28/10/20





25 Gb/s SERDES in 28 nm (work in progress...)

Motivations:

- Parallel to high-speed serial communication conversion and vice versa
- Time Division Multiplexing for area and power reduction
- Custom Current Mode Logic architecture for high-speed



Layout area: 60 x 190 μm² Power consumption: 100 mW Layout block





Future steps in 28 nm

- Electrical testing of the submitted 28 nm chip
- Radiation testing of the submitted 28 nm chip
- 25 Gb/s SERDES design conclusion

٠

...

- 25 GHz Phase Locked Loop design in 28 nm
- 25 Gb/s PIN diodes receiver design in 28 nm



